

ABSTRACT

PLASMA CVD DEVICE AND METHOD OF MANUFACTURING MAGNETIC
RECORDING MEDIUM

To suppress the generation of an abnormal discharge
5 while depositing a CVD film.

A plasma CVD device includes a chamber 102, an anode
104, a cathode 103, a holding portion which holds a substrate
to be deposited 101 which is arranged so as to face the
electrode surface 104a of the anode and the cathode, a plasma
10 wall 88 which is provided so as to cover a space 87, an
anti-adhesion member 91 which is arranged between a first
gap 81 between the anode and the plasma wall and a first inner
surface 102a of the chamber and a pedestal 92 which is arranged
between the anti-adhesion member and the back surface 104b
15 of the anode and which is electrically connected to the anode,
where the maximum diameter of each of the first gap, a second
gap 82 between the anode and the anti-adhesion member, a third
gap 83 between the back surface of the anode and the pedestal,
a fourth gap 84 between the plasma wall and the anti-adhesion
20 member and a fifth gap 85 between the anti-adhesion member
and the pedestal is equal to or less than 4 mm.

FIG. 1